

In the claims:

1. (Currently amended) A method of calibrating modificationmagnification of optical devices, comprising the steps of providing a mask with a predetermined pattern, projecting radiation through the mask so as to form a patterned projected image; and comparing a pattern of the projected image with a pattern of the mask to determine deviations of the projected image from the image of the mask, said providing including forming a mask by an optical source producing an interference pattern corresponding to the desired pattern of the mask.
2. (Original claim) A method as defined in claim 1, wherein said comparing includes comparing a size of the projected image with the size of the image on the mask.
3. (Original claim) A method as defined in claim 1, wherein said providing the mask includes providing a mask which has at least two fields each having a plurality of features spaced from one another in one direction so that the directions of spacing of the features in said two fields are transverse to one another.

4. (Original claim) A method as defined in claim 3, wherein said features in each of said field are evenly spaced from one another.

5. (Original claim) A method as defined in claim 3, wherein said features in each of said fields are parallel to one another.

6. (Original claim) A method as defined in claim 3; and further comprising arranging the mask so that said features of at least one of said fields are aligned with a principal axis of the optical device.

7. (Original claim) A method as defined in claim 3, wherein said features are arranged so that a spacing between the features of one of said fields is different from the spacing of said features of the other of said fields.

8. (Original claim) A method as defined in claim 1; and further comprising moving an article on which the image is projected relative to the optical device so as to produce a plurality of images with a plurality of patterns, said comparing includes comparing the plurality of patterns of the plurality of images with the pattern of the mask.

9. (Original claim) A method as defined in claim 1, wherein said obtaining of the projected image includes providing a substrate, projecting the pattern through the mask on the substrate, and obtaining the projected image on the substrate.

10. (Original claim) A method as defined in claim 1, wherein said obtaining of projected image includes passing the radiation through the mask and obtaining an electronic image with a pattern, said comparing includes comparing the pattern of the electronic image with the pattern of the mask.

11. (Original claim) A method as defined in claim 1, wherein said comparing includes comparing a deviation of a magnification of the pattern and the image relative to the pattern of the mask from a standard deviation.

Claims 13 and 14 cancelled.

14. (New claim) A method of calibrating magnification of optical devices, comprising the steps of providing a mask with a predetermined pattern, projecting radiation through the mask so as to form

a patterned projected image; and comparing a pattern of the projected image with a pattern of the mask to determine deviations of the projected image from the image of the mask, said providing includes producing the mask by an optical source which generates an interference pattern and acts on a chemical substance to cause etching of corresponding areas of the mask so as to produce the desired pattern of the mask.